


**PRODUCTION OF COLLOIDAL SILICA****Publication number:** JP4074707 (A)**Publication date:** 1992-03-10**Inventor(s):** KOJIMA YOSHIO**Applicant(s):** MONSANTO JAPAN**Classification:****- international:** C01B33/143; C01B33/151; C01B33/00; (IPC1-7): C01B33/143**- European:****Application number:** JP19900179644 19900709**Priority number(s):** JP19900179644 19900709**Also published as:** JP2843655 (B2)**Abstract of JP 4074707 (A)**

**PURPOSE:**To readily obtain colloidal silica not containing an alkali metal by adding an oxidizing agent and a mineral acid to a silicic acid aqueous solution free from the alkali metal and allowing the silica particles to grow in the presence of a basic organic compound, etc. **CONSTITUTION:**An alkali metal is removed from a silicic acid alkali metal salt aqueous solution having a silicic acid content of 1-10 wt.% and a pH of  $\geq 7$ . The treated solution is mixed with an oxidizing agent (hydrogen peroxide, hypochlorous acid or nitrous acid) to accelerate the polycondensation reaction of the silicic acid salt, and simultaneously mixed with a mineral acid (e.g. hydro chloric acid, nitric acid or hydrobromic acid) to stabilize a silicic acid aqueous solution.; One part of the stabilized aqueous solution is aged and mixed with ammonia or a basic organic compound to prepare a basic silicic aqueous solution. The silicic acid aqueous solution is dropwisely mixed with the remaining silicic acid aqueous solution containing the oxidizing agent and a mineral acid.

---

Data supplied from the **esp@cenet** database — Worldwide